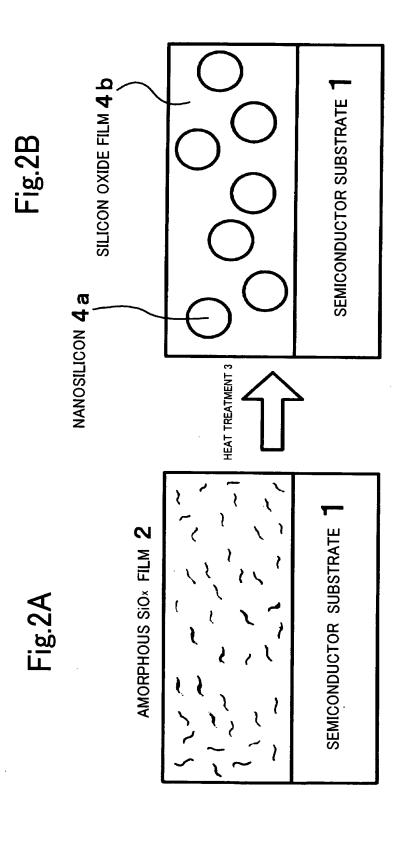
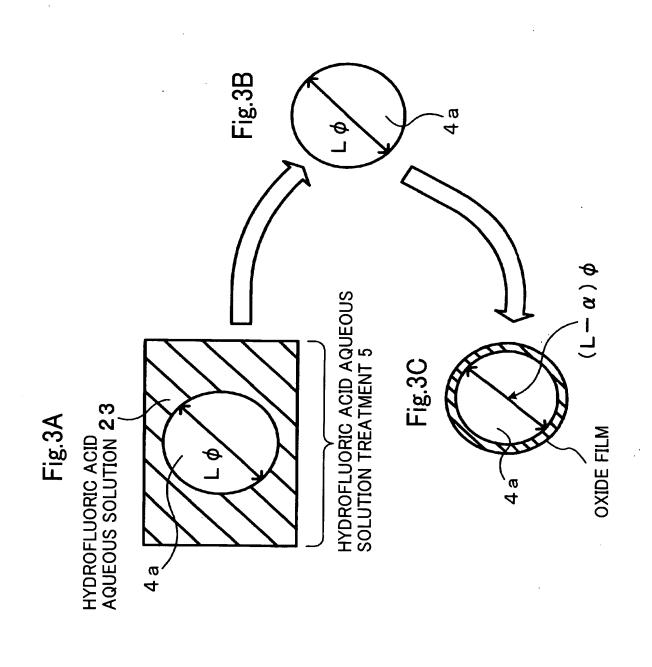
SEMICONDUCTOR SUBSTRATE HYDROFLUORIC ACID AQUEOUS 5 SOLUTION TREATMENT NATURAL OXIDATION TREATMENT 9 THERMAL OXIDATION 6 HYDROFLUORIC ACID AQUEOUS SOLUTION TREATMENT 5 R 4b SILICON OXIDE FILM 23 HYDROFLUORIC ACID AQUEOUS SOLUTION SEMICONDUCTOR SUBSTRATE 4a NANOSILICON 22 RESIN CONTAINER

Fig.1B

Fig.1A





500 600 700 WAVELENGTH (nm) GREEN RED 400 0.5 PL STRENGTH (ARBITRARY SCALE)

800

700

